

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	21446	anthracene	US-PGPUB; USPAT	OR	ON	2006/08/14 15:39
L2	9629	anthracene and synthesis	US-PGPUB; USPAT	OR	ON	2006/08/14 15:39
L3	9287	anthracene and making	US-PGPUB; USPAT	OR	ON	2006/08/14 15:39
L4	11283	anthracene and make	US-PGPUB; USPAT	OR	ON	2006/08/14 15:39
L5	673162	anthracene and ammonium salt	US-PGPUB; USPAT	OR	ON	2006/08/14 15:40
L6	8525	anthracene and ammonium and salt	US-PGPUB; USPAT	OR	ON	2006/08/14 15:40
L7	4223	anthracene and ammonium and salt and making	US-PGPUB; USPAT	OR	ON	2006/08/14 15:40
L8	464	l7 and alkylating	US-PGPUB; USPAT	OR	ON	2006/08/14 15:40
L9	410	l7 and alkylating and ether	US-PGPUB; USPAT	OR	ON	2006/08/14 15:40
L10	76	l7 and alkylating and ether and phosphonium	US-PGPUB; USPAT	OR	ON	2006/08/14 15:41
L11	0	anthracenediol and l10	US-PGPUB; USPAT	OR	ON	2006/08/14 15:42
L12	36	anthracenediol	US-PGPUB; USPAT	OR	ON	2006/08/14 15:42
L13	0	l10 and l12	US-PGPUB; USPAT	OR	ON	2006/08/14 15:42
L14	671835	l12 and ammonium salt	US-PGPUB; USPAT	OR	ON	2006/08/14 15:42
L15	6	l12 and ammonium ADJ salt	US-PGPUB; USPAT	OR	ON	2006/08/14 15:43
S1	1	"6696112".pn.	US-PGPUB; USPAT	OR	ON	2006/08/14 12:06
S2	5	"539807".ap.	US-PGPUB; USPAT	OR	ON	2006/08/14 15:38

10/539,807 8-14-2006 Yung chu

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NEWS 8 MAY 30 IPC 8 Rolled-up Core codes added to CA/Caplus and  
USPATFULL/USPAT2  
NEWS 9 MAY 30 The F-Term thesaurus is now available in CA/Caplus  
NEWS 10 JUN 02 The first reclassification of IPC codes now complete in  
INPADOC  
NEWS 11 JUN 26 TULSA/TULSA2 reloaded and enhanced with new search and  
and display fields  
NEWS 12 JUN 28 Price changes in full-text patent databases EPFULL and PCTFULL  
NEWS 13 JUL 11 CHEMSAFE reloaded and enhanced  
NEWS 14 JUL 14 FSTA enhanced with Japanese patents  
NEWS 15 JUL 19 Coverage of Research Disclosure reinstated in DWPI  
NEWS 16 AUG 09 INSPEC enhanced with 1898-1968 archive  
  
NEWS EXPRESS JUNE 30 CURRENT WINDOWS VERSION IS V8.01b, CURRENT  
MACINTOSH VERSION IS V6.0c(ENG) AND V6.0Jc(JP),  
AND CURRENT DISCOVER FILE IS DATED 26 JUNE 2006.  
  
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\* \* \* \* \* STN Columbus \* \* \* \* \*

FILE 'HOME' ENTERED AT 08:28:40 ON 14 AUG 2006

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=> file reg

COST IN U.S. DOLLARS

FULL ESTIMATED COST

SINCE FILE	TOTAL
ENTRY	SESSION
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DICTIONARY FILE UPDATES: 11 AUG 2006 HIGHEST RN 900864-99-5

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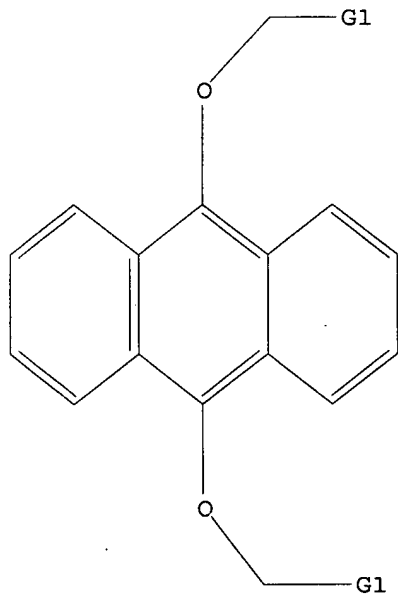
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experimental property data in the original document. For information  
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<http://www.cas.org/ONLINE/UG/regprops.html>

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Uploading C:\Documents and Settings\ychu\Desktop\Case\10539807\10539807.str

L1 STRUCTURE UPLOADED

=> d  
L1 HAS NO ANSWERS  
L1 STR



G1 Ak,Cb

Structure attributes must be viewed using STN Express query preparation.

=> s 11  
SAMPLE SEARCH INITIATED 08:29:15 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED -- 739 TO ITERATE

100.0% PROCESSED 739 ITERATIONS 25 ANSWERS  
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*  
BATCH \*\*COMPLETE\*\*  
PROJECTED ITERATIONS: 13150 TO 16410  
PROJECTED ANSWERS: 200 TO 800

L2 25 SEA SSS SAM L1

=> s l1 full  
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100.0% PROCESSED 15657 ITERATIONS 454 ANSWERS  
SEARCH TIME: 00.00.01

L3 454 SEA SSS FUL L1

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	167.38	167.59

FILE 'CAPLUS' ENTERED AT 08:30:07 ON 14 AUG 2006  
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FILE LAST UPDATED: 13 Aug 2006 (20060813/ED)

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<http://www.cas.org/infopolicy.html>

=> s l3  
L4 366 L3

=> s l4 and quaternary ammonium  
127577 QUATERNARY  
339 QUATERNARIES  
127720 QUATERNARY  
(QUATERNARY OR QUATERNARIES)  
370638 AMMONIUM  
402 AMMONIUMS  
370782 AMMONIUM  
(AMMONIUM OR AMMONIUMS)  
63227 QUATERNARY AMMONIUM  
(QUATERNARY (W) AMMONIUM)

L5

## 3 L4 AND QUATERNARY AMMONIUM

=&gt; d ibib abs hitstr tot

L5 ANSWER 1 OF 3 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2003:271685 CAPLUS

DOCUMENT NUMBER: 138:287414

TITLE: Preparation of hydroquinone alkyl ethers

INVENTOR(S): Kubo, Hideo; Yamaguchi, Katsuji; Shirai, Akihiro

PATENT ASSIGNEE(S): Nippon Soda Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003104926	A2	20030409	JP 2001-299629	20010928
PRIORITY APPLN. INFO.:			JP 2001-299629	20010928

OTHER SOURCE(S): CASREACT 138:287414

AB Title compds., useful as sensitizers for photopolymn., etc. (no data), are prepd. by alkylation of hydroquinones by C.gtoeq.3 alkylating agents in the presence of bases and quaternary ammonium salts having C.gtoeq.5 substituents on N. Anthraquinone was alkylated by BuI in THF/H<sub>2</sub>O in the presence of trioctylmethylammonium chloride, Na<sub>2</sub>S<sub>2</sub>O<sub>4</sub>, and NaOH at 40-50.degree. for 5 h to give 85% 9,10-dibutoxyanthracene.

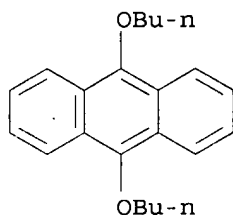
IT 76275-14-4P

RL: IMF (Industrial manufacture); SPN (Synthetic preparation); PREP (Preparation)

(prepn. of hydroquinone alkyl ethers from hydroquinones using quaternary ammonium salts)

RN 76275-14-4 CAPLUS

CN Anthracene, 9,10-dibutoxy- (9CI) (CA INDEX NAME)



L5 ANSWER 2 OF 3 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2003:271684 CAPLUS

DOCUMENT NUMBER: 138:287413

TITLE: Preparation of anthracene diethers

INVENTOR(S): Nakano, Hironori; Honda, Hiroyuki; Numata, Shigeaki

PATENT ASSIGNEE(S): Kawasaki Kasei Chemicals, Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 7 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003104925	A2	20030409	JP 2001-299128	20010928

Current Application

CA 2510270	AA	20040708	CA 2002-2510270	20021219
WO 2004056734	A1	20040708	WO 2002-JP13314	20021219
WO 2004056734	C1	20050804		

W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW

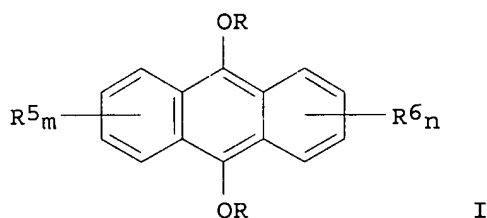
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AU 2002357616	A1	20040714	AU 2002-357616	20021219
EP 1574493	A1	20050914	EP 2002-808287	20021219

R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, SK

US 2006079721	A1	20060413	US 2005-539807	20050620
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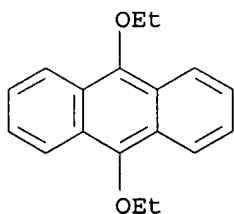
OTHER SOURCE(S): MARPAT 138:287413  
GI



AB Anthracene diethers I. (R = alkyl, allyl, aryl, benzyl, hydroxyalkyl, alkoxyalkyl; R5, R6 = inert group; m, n = 0-4), useful as sensitizers for photocurable compns. (no data), are prepd. by reaction of 9,10-anthracenediols with etherifying agents in aq. media contg. alkalies and quaternary ammonium or phosphonium compds. 9,10-Anthracenediol Na salt was etherified with BuBr in H2O/MEK in the presence of Bu4NBr at 70.degree. for 4 h to give 90% 9,10-dibutoxyanthracene.

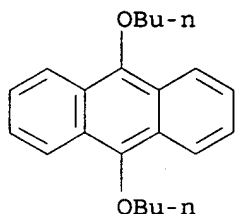
IT 68818-86-0P, 9,10-Diethoxyanthracene 76275-14-4P  
479412-73-2P  
RL: IMF (Industrial manufacture); SPN (Synthetic preparation); PREP (Preparation)  
(prepn. of anthracene diethers from anthracenediols using quaternary ammonium or phosphonium compds.)

RN 68818-86-0 CAPLUS  
CN Anthracene, 9,10-diethoxy- (6CI, 9CI) (CA INDEX NAME)



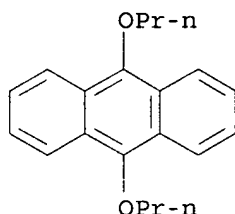
RN 76275-14-4 CAPLUS

CN Anthracene, 9,10-dibutoxy- (9CI) (CA INDEX NAME)



RN 479412-73-2 CAPLUS

CN Anthracene, 9,10-dipropoxy- (9CI) (CA INDEX NAME)



*for allowance close  
art*  
*Composition*

L5 ANSWER 3 OF 3 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 1987:59428 CAPLUS

DOCUMENT NUMBER: 106:59428

TITLE: Liquid crystal compositions

INVENTOR(S): Horimoto, Hikari; Mizutani, Yukio; Ogata, Takayuki

PATENT ASSIGNEE(S): Tokuyama Soda Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 13 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 61136584	A2	19860624	JP 1984-257349	19841207
JP 03080833	B4	19911226		

PRIORITY APPLN. INFO.: JP 1984-257349 19841207

AB The claimed liq. crystal-like comps. contain (1) a quaternary ammonium compd. having .gtoreq.2 linear hydrophobic groups or .gtoreq.1 hydrophobic group contg. stiff part within the chain and (2) a phosphoric group-contg. compd. having .gtoreq.2 linear hydrophobic groups. The liq. crystal-like comps. give membranes which show good water resistance and liq. crystal characteristics. The comps. are useful in prepg. synthetic biomembranes, display devices, and membranes for various sensors. Thus, a di(n-octadecyl)dimethylammonium bromide soln. and a di(n-dodecyl)monohydrogen phosphate soln. were mixed to give white ppt. which showed small soly. in water and showed liq. crystal phase at 56-115.

IT 106347-17-5

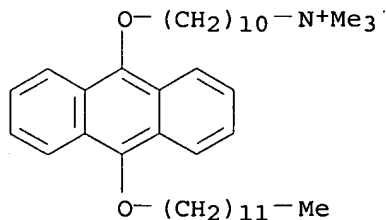
RL: PRP (Properties)  
(prepns. of, as liq. crystal compds.)

RN 106347-17-5 CAPLUS

CN 1-Decanaminium, 10-[[10-(dodecyloxy)-9-anthracenyl]oxy]-N,N,N-trimethyl-, dioctadecyl phosphate (9CI) (CA INDEX NAME)

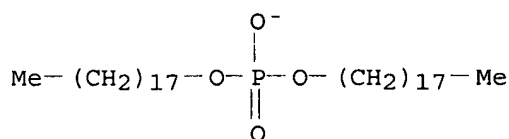
CM 1

CRN 106347-16-4  
CMF C39 H62 N O2



CM 2

CRN 84841-00-9  
CMF C36 H74 O4 P



=> s l4 and quaternary phosphonium  
127577 QUATERNARY  
339 QUATERNARIES  
127720 QUATERNARY  
(QUATERNARY OR QUATERNARIES)  
15919 PHOSPHONIUM  
80 PHOSPHONIUMS  
15942 PHOSPHONIUM  
(PHOSPHONIUM OR PHOSPHONIUMS)  
1216 QUATERNARY PHOSPHONIUM  
(QUATERNARY(W) PHOSPHONIUM)  
L6 0 L4 AND QUATERNARY PHOSPHONIUM

=> s l4 and phase transfer  
1690902 PHASE  
353345 PHASES  
1839674 PHASE  
(PHASE OR PHASES)  
781065 TRANSFER  
25566 TRANSFERS  
793479 TRANSFER  
(TRANSFER OR TRANSFERS)  
14182 PHASE TRANSFER  
(PHASE(W) TRANSFER)  
L7 1 L4 AND PHASE TRANSFER

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L7 ANSWER 1 OF 1 CAPLUS COPYRIGHT 2006 ACS on STN  
ACCESSION NUMBER: 2003:271685 CAPLUS  
DOCUMENT NUMBER: 138:287414  
TITLE: Preparation of hydroquinone alkyl ethers  
INVENTOR(S): Kubo, Hideo; Yamaguchi, Katsuji; Shirai, Akihiro



PATENT ASSIGNEE(S): Nippon Soda Co., Ltd., Japan  
 SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.  
 CODEN: JKXXAF  
 DOCUMENT TYPE: Patent  
 LANGUAGE: Japanese  
 FAMILY ACC. NUM. COUNT: 1  
 PATENT INFORMATION:

*duplicate 1/3*

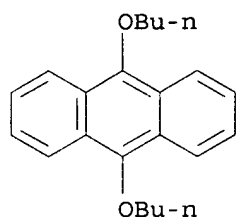
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003104926	A2	20030409	JP 2001-299629	20010928
PRIORITY APPLN. INFO.:			JP 2001-299629	20010928

OTHER SOURCE(S): CASREACT 138:287414

AB Title compds., useful as sensitizers for photopolymn., etc. (no data), are prepd. by alkylation of hydroquinones by C.gtoreq.3 alkylating agents in the presence of bases and quaternary ammonium salts having C.gtoreq.5 substituents on N. Anthraquinone was alkylated by BuI in THF/H2O in the presence of trioctylmethylammonium chloride, Na2S2O4, and NaOH at 40-50.degree. for 5 h to give 85% 9,10-dibutoxyanthracene.

IT 76275-14-4P  
 RL: IMF (Industrial manufacture); SPN (Synthetic preparation); PREP (Preparation)  
 (prepn. of hydroquinone alkyl ethers from hydroquinones using quaternary ammonium salts)

RN 76275-14-4 CAPLUS  
 CN Anthracene, 9,10-dibutoxy- (9CI) (CA INDEX NAME)



=> s 14 and quaternary salt  
 127577 QUATERNARY  
 339 QUATERNARIES  
 127720 QUATERNARY  
 (QUATERNARY OR QUATERNARIES)  
 771808 SALT  
 597517 SALTS  
 1148926 SALT  
 (SALT OR SALTS)  
 6851 QUATERNARY SALT  
 (QUATERNARY (W) SALT)  
 L8 0 L4 AND QUATERNARY SALT

=> s 14 and etherifying agent  
 1025 ETHERIFYING  
 793909 AGENT  
 1154928 AGENTS  
 1624410 AGENT  
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 (ETHERIFYING (W) AGENT)  
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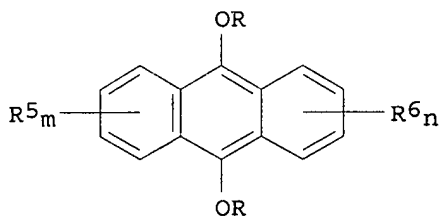
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L9 ANSWER 1 OF 1 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2003:271684 CAPLUS  
DOCUMENT NUMBER: 138:287413  
TITLE: Preparation of anthracene diethers  
INVENTOR(S): Nakano, Hironori; Honda, Hiroyuki; Numata, Shigeaki  
PATENT ASSIGNEE(S): Kawasaki Kasei Chemicals, Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 7 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

*Current application*

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003104925	A2	20030409	JP 2001-299128	20010928
CA 2510270	AA	20040708	CA 2002-2510270	20021219
WO 2004056734	A1	20040708	WO 2002-JP13314	20021219
WO 2004056734	C1	20050804		
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW				
RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG				
AU 2002357616	A1	20040714	AU 2002-357616	20021219
EP 1574493	A1	20050914	EP 2002-808287	20021219
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, SK				
US 2006079721	A1	20060413	US 2005-539807	20050620
PRIORITY APPLN. INFO.:			JP 2001-299128	A 20010928
			WO 2002-JP13314	W 20021219
OTHER SOURCE(S):		MARPAT 138:287413		
GI				



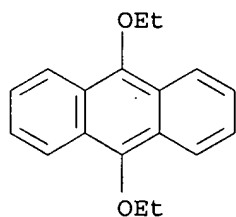
AB Anthracene diethers I (R = alkyl, allyl, aryl, benzyl, hydroxyalkyl, alkoxyalkyl; R5, R6 = inert group; m, n = 0-4), useful as sensitizers for photocurable compns. (no data), are prepd. by reaction of 9,10-anthracenediols with etherifying agents in aq. media contg. alkalies and quaternary ammonium or phosphonium compds. 9,10-Anthracenediol Na salt was etherified with BuBr in H2O/MEK in the presence of Bu4NBr at 70.degree. for 4 h to give 90% 9,10-dibutoxyanthracene.

IT 68818-86-0P, 9,10-Diethoxyanthracene 76275-14-4P  
479412-73-2P  
RL: IMF (Industrial manufacture); SPN (Synthetic preparation); PREP (Preparation)

(prepn. of anthracene diethers from anthracenediols using quaternary ammonium or phosphonium compds.)

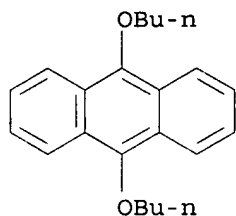
RN 68818-86-0 CAPLUS

CN Anthracene, 9,10-diethoxy- (6CI, 9CI) (CA INDEX NAME)



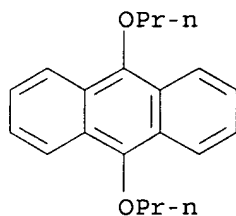
RN 76275-14-4 CAPLUS

CN Anthracene, 9,10-dibutoxy- (9CI) (CA INDEX NAME)



RN 479412-73-2 CAPLUS

CN Anthracene, 9,10-dipropoxy- (9CI) (CA INDEX NAME)



=> s l4 and phosphonium

15919 PHOSPHONIUM

80 PHOSPHONIUMS

15942 PHOSPHONIUM

(PHOSPHONIUM OR PHOSPHONIUMS)

L10 3 L4 AND PHOSPHONIUM

=> d ibib abs hitstr tot

L10 ANSWER 1 OF 3 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2005:116518 CAPLUS

DOCUMENT NUMBER: 142:200135

TITLE: UV-curable coating compositions for food or soft drink cans or bottles and their coated products

INVENTOR(S): Nakajima, Yoshimoto

PATENT ASSIGNEE(S): Toyo Ink Mfg. Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 28 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2005036152	A2	20050210	JP 2003-276500	20030718
PRIORITY APPLN. INFO.:			JP 2003-276500	20030718

OTHER SOURCE(S): MARPAT 142:200135

AB Title compns. contain (A) photo cationic polymn. initiators selected from iodonium, sulfonium, sulfoxonium, and/or phosphonium salts, (B) 9,10-dialkoxyanthracenes (with C1-8 alkoxy groups substituted at 9 and 10 positions and C1-4 alkyl-substituted or unsubstituted 1-4 and 5-8 positions) as photo sensitizers, (C) room temp. solid epoxy compds. (contg. Me-substituted phenol, epichlorohydrin, and HCHO units), (D) alicyclic epoxy group-contg. cationic polymn. compds., and (E) pigments at A/(A + B + C + D + E) of 1.5-4.0% and C/(A + B + C + D + E) of 1-10%, and preferably E/(A + B + C + D + E) of .gtoreq.40% for TiO2 and .gtoreq.10% for Al pigment. A Sn-plated steel and PET laminate was coated with a white compn. contg. Cyacure UVI 6990 3, 9,10-dibutoxyanthracene 0.3, YDCN 704 5, Cyacure UVR 6110 41.70, and TiO2 50 parts and UV-cured at 40-70% relative humidity over 10-30 s to form a hard film with excellent adhesion.

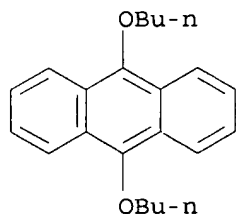
IT 76275-14-4

RL: CAT (Catalyst use); USES (Uses)

(photosensitizer; UV-curable alicyclic epoxy coatings contg. onium cationic initiators and anthracene photo sensitizers for food cans or bottles)

RN 76275-14-4 CAPLUS

CN Anthracene, 9,10-dibutoxy- (9CI) (CA INDEX NAME)



L110 ANSWER 2 OF 3 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2003:271684 CAPLUS

DOCUMENT NUMBER: 138:287413

TITLE: Preparation of anthracene diethers

INVENTOR(S): Nakano, Hironori; Honda, Hiroyuki; Numata, Shigeaki

PATENT ASSIGNEE(S): Kawasaki Kasei Chemicals, Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 7 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003104925	A2	20030409	JP 2001-299128	20010928
CA 2510270	AA	20040708	CA 2002-2510270	20021219
WO 2004056734	A1	20040708	WO 2002-JP13314	20021219
WO 2004056734	C1	20050804		

W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN,

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duplicate

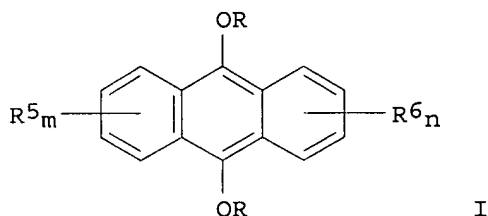
CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH,  
 GM, HR, HU, ID, IL, IN, IS, KE, KG, KR, KZ, LC, LK, LR, LS, LT,  
 LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT,  
 RO, RU, SC, SD, SE, SG, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG,  
 US, UZ, VC, VN, YU, ZA, ZM, ZW  
 RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY,  
 KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES,  
 FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SI, SK, TR, BF, BJ, CF,  
 CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG

AU 2002357616 A1 20040714 AU 2002-357616 20021219  
 EP 1574493 A1 20050914 EP 2002-808287 20021219

R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,  
 IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, SK

US 2006079721 A1 20060413 US 2005-539807 20050620  
 PRIORITY APPLN. INFO.: JP 2001-299128 A 20010928  
 WO 2002-JP13314 W 20021219

OTHER SOURCE(S): MARPAT 138:287413  
 GI



AB Anthracene diethers I (R = alkyl, allyl, aryl, benzyl, hydroxyalkyl, alkoxyalkyl; R5, R6 = inert group; m, n = 0-4), useful as sensitizers for photocurable compns. (no data), are prepd. by reaction of 9,10-anthracenediols with etherifying agents in aq. media contg. alkalies and quaternary ammonium or phosphonium compds. 9,10-Anthracenediol Na salt was etherified with BuBr in H2O/MEK in the presence of Bu4NBr at 70.degree. for 4 h to give 90% 9,10-dibutoxyanthracene.

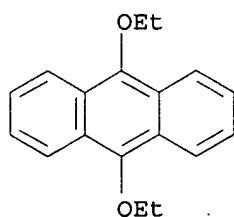
IT 68818-86-0P, 9,10-Diethoxyanthracene 76275-14-4P  
 479412-73-2P

RL: IMF (Industrial manufacture); SPN (Synthetic preparation); PREP (Preparation)

(prepn. of anthracene diethers from anthracenediols using quaternary ammonium or phosphonium compds.)

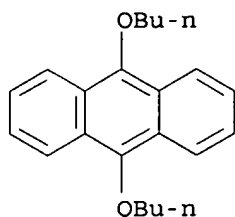
RN 68818-86-0 CAPLUS

CN Anthracene, 9,10-diethoxy- (6CI, 9CI) (CA INDEX NAME)

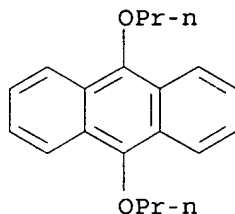


RN 76275-14-4 CAPLUS

CN Anthracene, 9,10-dibutoxy- (9CI) (CA INDEX NAME)



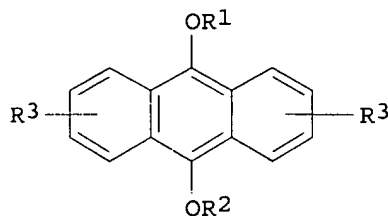
RN 479412-73-2 CAPLUS  
CN Anthracene, 9,10-dipropoxy- (9CI) (CA INDEX NAME)



L10 ANSWER 3 OF 3 CAPLUS COPYRIGHT 2006 ACS on STN  
ACCESSION NUMBER: 2000:503506 CAPLUS  
DOCUMENT NUMBER: 133:136808  
TITLE: Radiation-curable compositions and manufacture of coatings therefrom  
INVENTOR(S): Maruyama, Tsutomu  
PATENT ASSIGNEE(S): Kansai Paint Co., Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 14 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000204284	A2	20000725	JP 1999-8726	19990118
PRIORITY APPLN. INFO.:			JP 1999-8726	19990118
OTHER SOURCE(S):	MARPAT 133:136808			
GI				

*Handwritten notes:*  
New composition  
Not related  
may



I

AB The compns. contain (A) photosensitizers I (R1, R2 = C1-8-alkyl; R3 = H, C1-4-alkyl) 0.01-5, (B) photo-cation initiators selected from iodonium salts, sulfonium salts, and phosphonium salts 0.1-20, and (C) cationically photopolymerizable compds. 100 parts. Thus, a compn. contg. 9,10-diethoxyanthracene 1, bis(4-tert-butylphenyl)iodonium hexafluorophosphate (BBI 102) 1, and 3,4-epoxycyclohexylmethyl

3,4-epoxycyclohexanecarboxylate (UVR 6110) 100 parts was applied on a substrate and radiation-cured to give a coating, showing spectral sensitivity 205-450 nm, gel fraction 87%, and pencil hardness 3-4 H.

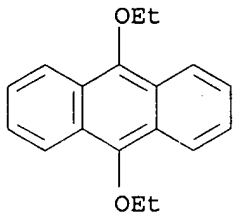
IT 68818-86-0, 9,10-Diethoxyanthracene 76275-14-4  
205515-07-7, 2-Ethyl-9,10-diethoxyanthracene 205515-11-3  
, 2-Methyl-9,10-diethoxyanthracene

RL: CAT (Catalyst use); USES (Uses)

(photosensitizer; radiation-curable coating compns. with good curability and hardness)

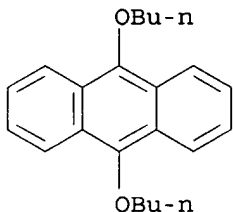
RN 68818-86-0 CAPLUS

CN Anthracene, 9,10-diethoxy- (6CI, 9CI) (CA INDEX NAME)



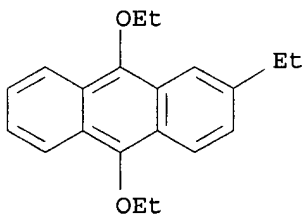
RN 76275-14-4 CAPLUS

CN Anthracene, 9,10-dibutoxy- (9CI) (CA INDEX NAME)



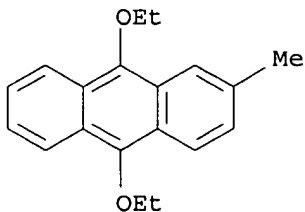
RN 205515-07-7 CAPLUS

CN Anthracene, 9,10-diethoxy-2-ethyl- (9CI) (CA INDEX NAME)



RN 205515-11-3 CAPLUS

CN Anthracene, 9,10-diethoxy-2-methyl- (9CI) (CA INDEX NAME)



=> s 14 and amonium salt

10 AMONIUM  
771808 SALT  
597517 SALTS  
1148926 SALT  
(SALT OR SALTS)  
2 AMONIUM SALT  
(AMONIUM(W)SALT)  
L11 0 L4 AND AMONIUM SALT

=> s 14 and ammonium

370638 AMMONIUM  
402 AMMONIUMS  
370782 AMMONIUM  
(AMMONIUM OR AMMONIUMS)  
L12 9 L4 AND AMMONIUM

=> d ibib abs hitstr tot

L12 ANSWER 1 OF 9 CAPLUS COPYRIGHT 2006 ACS on STN  
ACCESSION NUMBER: 2005:1310229 CAPLUS  
DOCUMENT NUMBER: 144:57628  
TITLE: Photocurable dental composition  
INVENTOR(S): Frances, Jean-Marc  
PATENT ASSIGNEE(S): Fr.  
SOURCE: U.S. Pat. Appl. Publ., 30 pp.  
CODEN: USXXCO  
DOCUMENT TYPE: Patent  
LANGUAGE: English  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2005277705	A1	20051215	US 2005-125133	20050510
FR 2872409	A1	20060106	FR 2004-7210	20040630
WO 2005120439	A1	20051222	WO 2005-FR1049	20050428

W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SM, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW

RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG

PRIORITY APPLN. INFO.:  
FR 2004-5176 A 20040513  
FR 2004-7210 A 20040630  
US 2004-599021P P 20040806

OTHER SOURCE(S): MARPAT 144:57628

AB Dental compns. are described which are photocurable by radiation with a wavelength greater than 390 nm. The compns. include a cationically active compd., a dental filler, optionally a dispersant, a cationic photoinitiator and a photosensitizer which is a thioxanthone salt substituted by at least one group contg. an ammonium function. The compn. has the advantage of remedying the color stability problems of finished dental products after crosslinking. For example, dental composites comprising photosensitizer based on thioxanthenes contg. ammonium functionality, gave rise to an increased coloring

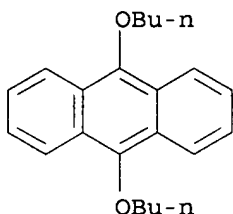


stability. An initial pink color change was obsd. with the comparative compn. comprising photosensitizer based on chloropropoxythioxanthone (CPTX), even at a low level of 60 ppm, which attenuates over time but which was still measurable after 5 days. In contrast, the use of thioxanthenes contg. ammonium functionality, did not give rise to this coloration defect at a low level and, surprisingly, made it possible to preserve a greater color stability.

IT 76275-14-4, 9,10-Dibutoxyanthracene  
 RL: CAT (Catalyst use); USES (Uses)  
 (PS-39; photocurable dental compn. comprising thioxanthone photosensitizer with increased color stability)

RN 76275-14-4 CAPLUS

CN Anthracene, 9,10-dibutoxy- (9CI) (CA INDEX NAME)



L12 ANSWER 2 OF 9 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2004:118389 CAPLUS

DOCUMENT NUMBER: 140:147419

TITLE: Positive-working photosensitive heat-resistant resin precursor compositions for semiconductor devices

INVENTOR(S): Yumiba, Tomoyuki; Suwa, Atsushi; Tomikawa, Masao

PATENT ASSIGNEE(S): Toray Industries, Inc., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 23 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004045477	A2	20040212	JP 2002-199583	20020709
PRIORITY APPLN. INFO.:			JP 2002-199583	20020709

OTHER SOURCE(S): MARPAT 140:147419

AB The compns. with improved adhesion to substrates after heat-curing for interlayer insulator films and surface protection films of semiconductor devices, contain (A) polymers having main units  
 [COR1(OH)p(CO2R3)nCONHR2(OH)q(CO2R4)oNH]m (R1, R2 = 2-8 valent C.gtoREQ.2 org. residue; R3, R4 = H, alkali metal ion, ammonium ion, C1-20 org. residue; m = 3-100,000; n, o = 0-2; p, q = 0-4; n + q > 0) and (B) compds. represented by R5R6C:N(CH2)a(SiR11R12O)bSiR13R14R15 or R7R8C:N(CH2)c(SiR16R17O)dSiR18R19(CH2)eN:CR9R10 (R5-R10 = C.gtoREQ.1 org. residue; R11-R19 = C1-6 hydrocarbonyl, C1-6 alkoxy; at least one of R11-R15 and one of R16-R19 = C1-6 alkoxy). Thus, a varnish contg. polyamic acid [prepd. from 4,4'-diaminodiphenyl ether, 1,3-bis(3-aminopropyl)tetramethyldisiloxane, pyromellitic anhydride, and 3,3',4,4'-benzophenonetetracarboxylic acid dianhydride] and 3-triethoxysilyl-N-(1,3-dimethylbutylidene)propylamine was applied on a Si wafer and heated to give a polyimide film showing high adhesion after pressure cooker test.

IT 119666-27-2

RL: CAT (Catalyst use); USES (Uses)

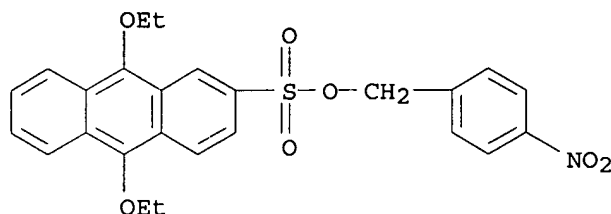
(photoacid generator; pos.-working photosensitive heat-resistant resin

*late and not OP P*

precursor compns. contg. aminoalkoxysilanes for semiconductor device  
insulator and protection films)

RN 119666-27-2 CAPLUS

CN 2-Anthracenesulfonic acid, 9,10-diethoxy-, (4-nitrophenyl)methyl ester  
(9CI) (CA INDEX NAME)



L12 ANSWER 3 OF 9 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2004:118071 CAPLUS

DOCUMENT NUMBER: 140:165070

TITLE: Heat-resistant resin precursor compositions and  
semiconductor devices therewith

INVENTOR(S): Yumiba, Tomoyuki; Minamihashi, Katsuya; Tomikawa,  
Masao

PATENT ASSIGNEE(S): Toray Industries, Inc., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 26 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

*Late / Not ODP*

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004043779	A2	20040212	JP 2003-119531	20030424
PRIORITY APPLN. INFO.:			JP 2002-126061	A 20020426

AB Title compns. comprise (A) polymers having repeating units  
[COR<sub>1</sub>(OH)<sub>p</sub>(COOR<sub>3</sub>)<sub>n</sub>CONHR<sub>2</sub>(OH)<sub>q</sub>(COOR<sub>4</sub>)<sub>o</sub>NH]<sub>m</sub> as main components and (B)  
compds. (Z<sub>1</sub>)<sub>a</sub>R<sub>5</sub>(Z<sub>2</sub>)<sub>b</sub>, wherein R<sub>1</sub>, R<sub>2</sub> = divalent-octavalent org. groups  
contg. .gtoreq.2 carbon atoms; R<sub>3</sub>, R<sub>4</sub> = H, alkali metal ion,  
ammonium ion, or C<sub>1</sub>-20 org. group; R<sub>5</sub> = structure contg. .gtoreq.2  
carbon atoms; m = 3-100,000 integer; n, o = 0-2 integer; p, q = 0-4  
integer (p + q > 0); Z<sub>1</sub> = .gtoreq.1 structure selected from NR<sub>6</sub>R<sub>7</sub>,  
N:CR<sub>8</sub>R<sub>9</sub>, NR<sub>10</sub>C(:O)R<sub>11</sub>, or NHCOR<sub>12</sub>OH; Z<sub>2</sub> = .gtoreq.1 structure selected  
from NR<sub>6</sub>R<sub>7</sub>, N:CR<sub>8</sub>R<sub>9</sub>, NR<sub>10</sub>C(:O)R<sub>11</sub>, NHCOR<sub>12</sub>OH, vinyl, ethenyl, mercapto, or  
hydroxy group; R<sub>6</sub>, R<sub>7</sub>, R<sub>8</sub>, R<sub>9</sub>, R<sub>10</sub> = H or C<sub>1</sub>-8 org. group; R<sub>11</sub>, R<sub>12</sub> = C<sub>1</sub>-8  
org. group; and a, b = .gtoreq.1 integer. Thus, 4,4'-diaminodiphenyl  
ether 19, 1,3-bis(3-aminopropyl)tetramethyldisiloxane 1.2, pyromellitic  
anhydride 10.8, and 3,3',4,4'-benzophenonetetracarboxylic dianhydride 15 g  
were reacted at room temp. for 6 h to give a polyamic acid varnish, 3%  
3-aminopropionitrile was added therein, applied on a copper-sputtered  
silicon wafer, a titanium-sputtered silicon wafer, and a gold-sputtered  
silicon wafer, and cured to give test pieces showing good adhesion between  
metal materials and a heat-resistant resin.

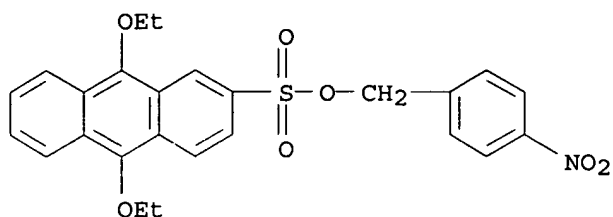
IT 119666-27-2

RL: CAT (Catalyst use); USES (Uses)

(photoacid generator; prepn. of heat-resistant resin precursor compns.  
for semiconductor devices)

RN 119666-27-2 CAPLUS

CN 2-Anthracenesulfonic acid, 9,10-diethoxy-, (4-nitrophenyl)methyl ester  
(9CI) (CA INDEX NAME)



L12 ANSWER 4 OF 9 CAPLUS COPYRIGHT 2006 ACS on STN  
 ACCESSION NUMBER: 2003:271685 CAPLUS  
 DOCUMENT NUMBER: 138:287414  
 TITLE: Preparation of hydroquinone alkyl ethers  
 INVENTOR(S): Kubo, Hideo; Yamaguchi, Katsuji; Shirai, Akihiro  
 PATENT ASSIGNEE(S): Nippon Soda Co., Ltd., Japan  
 SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.  
 CODEN: JKXXAF  
 DOCUMENT TYPE: Patent  
 LANGUAGE: Japanese  
 FAMILY ACC. NUM. COUNT: 1  
 PATENT INFORMATION:

*duplicate*

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003104926	A2	20030409	JP 2001-299629	20010928
PRIORITY APPLN. INFO.:			JP 2001-299629	20010928

OTHER SOURCE(S): CASREACT 138:287414

AB Title compds., useful as sensitizers for photopolymn., etc. (no data), are prepd. by alkylation of hydroquinones by C.gtoREQ.3 alkylating agents in the presence of bases and quaternary ammonium salts having C.gtoREQ.5 substituents on N. Anthraquinone was alkylated by BuI in THF/H2O in the presence of trioctylmethylammonium chloride, Na2S2O4, and NaOH at 40-50.degree. for 5 h to give 85% 9,10-dibutoxyanthracene.

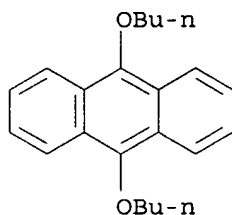
IT 76275-14-4P

RL: IMF (Industrial manufacture); SPN (Synthetic preparation); PREP (Preparation)

(prepn. of hydroquinone alkyl ethers from hydroquinones using quaternary ammonium salts)

RN 76275-14-4 CAPLUS

CN Anthracene, 9,10-dibutoxy- (9CI) (CA INDEX NAME)

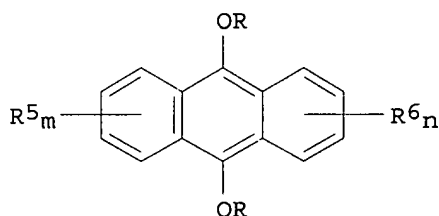


*Current app/duplicate*

L12 ANSWER 5 OF 9 CAPLUS COPYRIGHT 2006 ACS on STN  
 ACCESSION NUMBER: 2003:271684 CAPLUS  
 DOCUMENT NUMBER: 138:287413  
 TITLE: Preparation of anthracene diethers  
 INVENTOR(S): Nakano, Hironori; Honda, Hiroyuki; Numata, Shigeaki  
 PATENT ASSIGNEE(S): Kawasaki Kasei Chemicals, Ltd., Japan  
 SOURCE: Jpn. Kokai Tokkyo Koho, 7 pp.  
 CODEN: JKXXAF  
 DOCUMENT TYPE: Patent

LANGUAGE: Japanese  
 FAMILY ACC. NUM. COUNT: 1  
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003104925	A2	20030409	JP 2001-299128	20010928
CA 2510270	AA	20040708	CA 2002-2510270	20021219
WO 2004056734	A1	20040708	WO 2002-JP13314	20021219
WO 2004056734	C1	20050804		
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG				
AU 2002357616	A1	20040714	AU 2002-357616	20021219
EP 1574493	A1	20050914	EP 2002-808287	20021219
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, SK				
US 2006079721	A1	20060413	US 2005-539807	20050620
PRIORITY APPLN. INFO.:			JP 2001-299128	A 20010928
			WO 2002-JP13314	W 20021219
OTHER SOURCE(S):		MARPAT 138:287413		
GI				

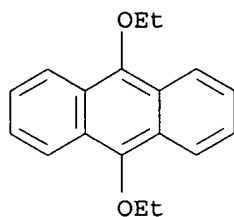


AB Anthracene diethers I (R = alkyl, allyl, aryl, benzyl, hydroxyalkyl, alkoxyalkyl; R5, R6 = inert group; m, n = 0-4), useful as sensitizers for photocurable compns. (no data), are prepd. by reaction of 9,10-anthracenediols with etherifying agents in aq. media contg. alkalies and quaternary ammonium or phosphonium compds. 9,10-Anthracenediol Na salt was etherified with BuBr in H2O/MEK in the presence of Bu4NBr at 70.degree. for 4 h to give 90% 9,10-dibutoxyanthracene.

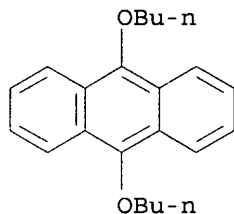
IT 68818-86-0P, 9,10-Diethoxyanthracene 76275-14-4P  
 479412-73-2P  
 RL: IMF (Industrial manufacture); SPN (Synthetic preparation); PREP (Preparation)  
 (prepn. of anthracene diethers from anthracenediols using quaternary ammonium or phosphonium compds.)

RN 68818-86-0 CAPLUS

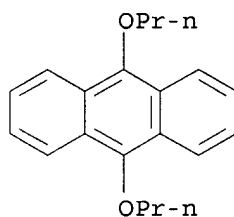
CN Anthracene, 9,10-diethoxy- (6CI, 9CI) (CA INDEX NAME)



RN 76275-14-4 CAPLUS  
 CN Anthracene, 9,10-dibutoxy- (9CI) (CA INDEX NAME)



RN 479412-73-2 CAPLUS  
 CN Anthracene, 9,10-dipropoxy- (9CI) (CA INDEX NAME)



L12 ANSWER 6 OF 9 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2002:36602 CAPLUS

DOCUMENT NUMBER: 136:103469

TITLE: Heat-resistant resin compositions useful for semiconductor devices with good adhesion and low absorbance

INVENTOR(S): Okuda, Ryoji; Fujiwara, Takenori; Tomikawa, Masao

PATENT ASSIGNEE(S): Toray Industries, Inc., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 17 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002012761	A2	20020115	JP 2001-112287	20010411
PRIORITY APPLN. INFO.:			JP 2000-129395	A 20000428

AB The comps. useful for surface protective and insulative uses for semiconductor devices contain triazine and/or vinyl group-contg. compds. and  $[\text{COR}_1(\text{OH})_p(\text{CO}_2\text{R}_3)_n\text{CONHR}_2(\text{OH})_q(\text{CO}_2\text{R}_4)_m\text{NH}]_m$  [ $\text{R}_1, \text{R}_2 = (2-8 \text{ valent}) \text{ org. group contg. } \geq 2 \text{ C atoms}; \text{R}_3, \text{R}_4 = \text{H, alkali metal ion, ammonium ion, C1-20 org. group}; m = 3-100,000; n = 0-2; p, q = 0-4; n + q > 0$ ]. Thus, cyanuric acid triallyl ester was mixed with a mixt.

*Composition/ not process for making*

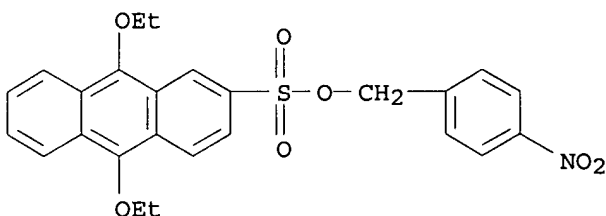
contg. 4,4'-diaminodiphenyl ether-pyromellitic anhydride-3,3',4,4'-benzophenonetetracarboxylic dianhydride copolymer, N,N-dimethylaminoethylmethacrylamide, N-phenylglycin, ethylene glycol dimethacrylate, and 3,3'-carbonylbis(7-diethylaminocoumalin), the resulting mixt. was applied on a glass substrate, dried, and cured to give a 1 .mu.m film showing absorbance 0.035 at 500 nm.

IT 119666-27-2

RL: MOA (Modifier or additive use); USES (Uses)  
(photoacid generator; heat-resistant resin compns. useful for semiconductor devices with good adhesion and low absorbance)

RN 119666-27-2 CAPLUS

CN 2-Anthracenesulfonic acid, 9,10-diethoxy-, (4-nitrophenyl)methyl ester  
(9CI) (CA INDEX NAME)



L12 ANSWER 7 OF 9 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 2002:10872 CAPLUS

DOCUMENT NUMBER: 136:93561

TITLE: Optical imaging device with flat display panels equipped with electrodes partially coated with dielectric material of positive-working light-sensitive polyimide

INVENTOR(S): Okuda, Ryoji; Fujimori, Shigeo; Oka, Tetsuo; Tomikawa, Masao

PATENT ASSIGNEE(S): Toray Industries, Inc., Japan

SOURCE: PCT Int. Appl., 52 pp.

CODEN: PIXXD2

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2002001922	A1	20020103	WO 2001-JP5466	20010626
W: KR, US				
RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR				
JP 2002091343	A2	20020327	JP 2001-189396	20010622
JP 2002116715	A2	20020419	JP 2001-189397	20010622
TW 525407	B	20030321	TW 2001-90115392	20010626
EP 1296540	A1	20030326	EP 2001-941258	20010626
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, FI, CY, TR				
US 2002162998	A1	20021107	US 2002-69769	20020228
US 6696112	B2	20040224		

PRIORITY APPLN. INFO.: JP 2000-194019 A 20000628  
WO 2001-JP5466 W 20010626

AB A display comprises a first electrode having an insulating layer in a manner such that a part of the first electrode is exposed, and a second electrode disposed so as to be opposed to the first electrode having the insulating layer, wherein the the insulating layer comprises a pos. photosensitive polyimide with structural unit [-CO-R1(OH)p(COOR3)n-CO-NH-

*display, not process*

*Not*

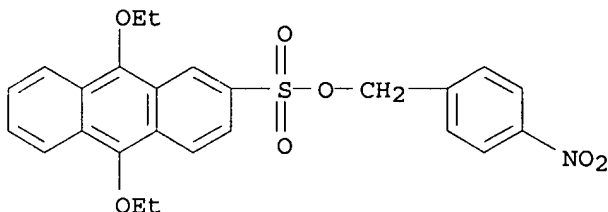
R2(OH)q(COOR4)o-NH-]m ( R1-2 = C,gtoreq.2 2-8 valent orgs.; R3-4 = H, alkali metal ion, ammonium ion, C1-20 orgs.; m = 3-100,000; n, o = 0-2 integer; p, q = 0-4 integer, p+q>0) and an agent generating an acid by a light. The optical imaging device has easily patterned polyimide insulating layer on the electrodes.

IT 119666-27-2

RL: RCT (Reactant); RACT (Reactant or reagent)  
(photoresist compn. for dielec. coating on electrodes of optical imaging devices)

RN 119666-27-2 CAPLUS

CN 2-Anthracenesulfonic acid, 9,10-diethoxy-, (4-nitrophenyl)methyl ester  
(9CI) (CA INDEX NAME)



*Not process for making*

REFERENCE COUNT: 9 THERE ARE 9 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L12 ANSWER 8 OF 9 CAPLUS COPYRIGHT 2006 ACS on STN

ACCESSION NUMBER: 1990:581220 CAPLUS

DOCUMENT NUMBER: 113:181220

TITLE: An aqueous base developable novel deep-UV resist for krypton fluoride (KrF) excimer laser lithography

AUTHOR(S): Murata, Makoto; Takahashi, Toshihiko; Koshiba, Mitsunobu; Kawamura, Shinichi; Yamaoka, Tsuguo  
CORPORATE SOURCE: Electron. Res. Lab., Japan Synth. Rubber Co., Ltd., Kawasaki, 215, Japan

SOURCE: Proceedings of SPIE-The International Society for Optical Engineering (1990), 1262(Adv. Resist Technol. Process. 7), 8-15

CODEN: PSISDG; ISSN: 0277-786X

DOCUMENT TYPE: Journal

LANGUAGE: English

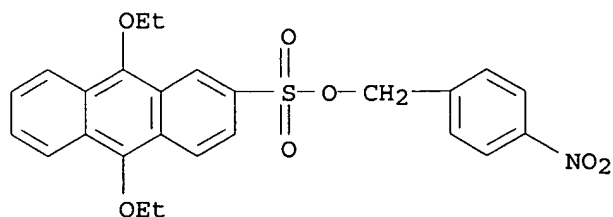
AB A novel deep-UV resist of poly(p-trimethylsilyloxystyrene) and p-nitrobenzyl 9-10-diethoxyanthracene-2-sulfonate is capable of resolving 0.3 .mu. lines and spaces with steep sidewalls at 0.8 .mu. thickness by a KrF excimer laser stepper. Wet development in a conventional tetramethylammonium hydroxide developer caused no crit. thickness loss in the unexposed area. Owing to its O plasma durability, this resist works as a top layer of a bilayer resist.

IT 119666-27-2

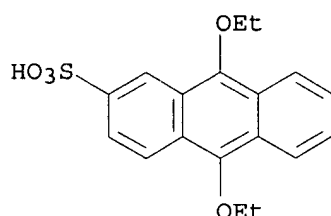
RL: USES (Uses)  
(excimer laser submicron lithog. deep-UV photoresist contg., aq. base developable)

RN 119666-27-2 CAPLUS

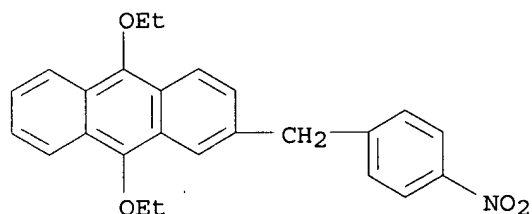
CN 2-Anthracenesulfonic acid, 9,10-diethoxy-, (4-nitrophenyl)methyl ester  
(9CI) (CA INDEX NAME)



IT 123131-61-3P, 9,10-Diethoxyanthracene-2-sulfonic acid  
 RL: RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)  
 (formation and reaction of, in deep-UV exposed submicron lithog.  
 photoresist)  
 RN 123131-61-3 CAPLUS  
 CN 2-Anthracenesulfonic acid, 9,10-diethoxy- (9CI) (CA INDEX NAME)



IT 129995-19-3, 9,10-Diethoxy-2-p-nitrobenzylanthracene  
 RL: USES (Uses)  
 (in deep-UV exposed submicron lithog. photoresist)  
 RN 129995-19-3 CAPLUS  
 CN Anthracene, 9,10-diethoxy-2-[(4-nitrophenyl)methyl]- (9CI) (CA INDEX NAME)



*Liquid composition,  
 but process for making*

L12 ANSWER 9 OF 9 CAPLUS COPYRIGHT 2006 ACS on STN  
 ACCESSION NUMBER: 1987:59428 CAPLUS  
 DOCUMENT NUMBER: 106:59428  
 TITLE: Liquid crystal compositions  
 INVENTOR(S): Horimoto, Hikari; Mizutani, Yukio; Ogata, Takayuki  
 PATENT ASSIGNEE(S): Tokuyama Soda Co., Ltd., Japan  
 SOURCE: Jpn. Kokai Tokkyo Koho, 13 pp.  
 CODEN: JKXXAF  
 DOCUMENT TYPE: Patent  
 LANGUAGE: Japanese  
 FAMILY ACC. NUM. COUNT: 1  
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 61136584	A2	19860624	JP 1984-257349	19841207
JP 03080833	B4	19911226		



PRIORITY APPLN. INFO.:

JP 1984-257349

19841207

AB The claimed liq. crystal-like compns. contain (1) a quaternary ammonium compd. having .gtoreq.2 linear hydrophobic groups or .gtoreq.1 hydrophobic group contg. stiff part within the chain and (2) a phosphoric group-contg. compd. having .gtoreq.2 linear hydrophobic groups. The liq. crystal-like compns. give membranes which show good water resistance and liq. crystal characteristics. The compns. are useful in prepg. synthetic biomembranes, display devices, and membranes for various sensors. Thus, a di(n-octadecyl)dimethylammonium bromide soln. and a di(n-dodecyl)monohydrogen phosphate soln. were mixed to give white ppt. which showed small soly. in water and showed liq. crystal phase at 56-115.

IT 106347-17-5

RL: PRP (Properties)

(prepns. of, as liq. crystal compds.)

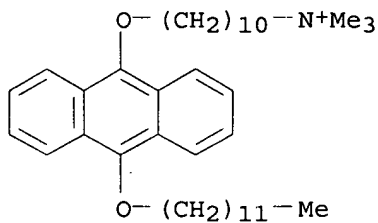
RN 106347-17-5 CAPLUS

CN 1-Decanaminium, 10-[[10-(dodecyloxy)-9-anthracenyl]oxy]-N,N,N-trimethyl-, dioctadecyl phosphate (9CI) (CA INDEX NAME)

CM 1

CRN 106347-16-4

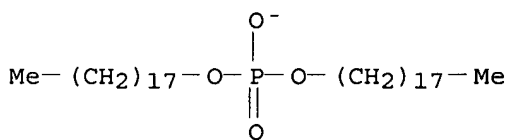
CMF C39 H62 N O2



CM 2

CRN 84841-00-9

CMF C36 H74 O4 P



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ENTER L#, L# RANGE, ALL, OR (END):yc10539807/a

YC10539807/A IS NOT A VALID L#, L# RANGE, OR ALL

Enter a valid L-number or L-number range for the items to be saved or

ALL to SAVE all session queries as an L-number list. To see all

L-numbers defined in this session, enter END. Then enter DISPLAY

HISTORY at an arrow prompt (=>).

ENTER L#, L# RANGE, ALL, OR (END):l4

ENTER NAME OR (END):yc10539807/a

ANSWER SET L4 HAS BEEN SAVED AS 'YC10539807/A'

HISTORY at an arrow prompt (=>).  
ENTER L#, L# RANGE, ALL, OR (END):14  
ENTER NAME OR (END):yc10539807/a  
ANSWER SET L4 HAS BEEN SAVED AS 'YC10539807/A'

=> s l4 and phase-transfer agent  
1690902 PHASE  
353345 PHASES  
1839674 PHASE  
(PHASE OR PHASES)  
781065 TRANSFER  
25566 TRANSFERS  
793479 TRANSFER  
(TRANSFER OR TRANSFERS)  
793909 AGENT  
1154928 AGENTS  
1624410 AGENT  
(AGENT OR AGENTS)  
659 PHASE-TRANSFER AGENT  
(PHASE(W) TRANSFER(W) AGENT)  
L13 0 L4 AND PHASE-TRANSFER AGENT

=> s l4 and phase transfer  
1690902 PHASE  
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1839674 PHASE  
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781065 TRANSFER  
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14182 PHASE TRANSFER  
(PHASE(W) TRANSFER)  
L14 1 L4 AND PHASE TRANSFER

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L14 ANSWER 1 OF 1 CAPLUS COPYRIGHT 2006 ACS on STN  
ACCESSION NUMBER: 2003:271685 CAPLUS Full-text  
DOCUMENT NUMBER: 138:287414  
TITLE: Preparation of hydroquinone alkyl ethers  
INVENTOR(S): Kubo, Hideo; Yamaguchi, Katsuji; Shirai, Akihiro  
PATENT ASSIGNEE(S): Nippon Soda Co., Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 2003104926	A2	20030409	JP 2001-299629	20010928
PRIORITY APPLN. INFO.:			JP 2001-299629	20010928

OTHER SOURCE(S): CASREACT 138:287414

AB Title compds., useful as sensitizers for photopolymn., etc. (no data), are  
prepd. by alkylation of hydroquinones by C.gto req.3 alkylating agents in the  
presence of bases and quaternary ammonium salts having C.gto req.5 substituents  
on N. Anthraquinone was alkylated by BuI in THF/H2O in the presence of

trioctylmethylammonium chloride, Na<sub>2</sub>S<sub>2</sub>O<sub>4</sub>, and NaOH at 40-50.degree. for 5 h to give 85% 9,10-dibutoxyanthracene.

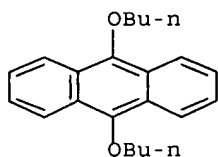
IT 76275-14-4P

RL: IMF (Industrial manufacture); SPN (Synthetic preparation); PREP (Preparation)

(prepn. of hydroquinone alkyl ethers from hydroquinones using quaternary ammonium salts)

RN 76275-14-4 CAPLUS

CN Anthracene, 9,10-dibutoxy- (9CI) (CA INDEX NAME)



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---Logging off of STN---

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Executing the logoff script...

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COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

139.15

306.74

DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)

SINCE FILE

TOTAL

ENTRY

SESSION

CA SUBSCRIBER PRICE

-13.50

-13.50

STN INTERNATIONAL LOGOFF AT 08:43:10 ON 14 AUG 2006